## Group-III nitride nanowire arrays made by sublimation for nanophotonic



**Fig 1** : SEM images of (a) bird's eye view of a NW array obtained after selective-area sublimation. (b) A NW transferred on SiN. (c) A subwavelength NW embedded in a slotted photonic crystal. (d) Room-temperature μPL spectra of the NW shown in panel b (blue line), a subwavelength NW transferred on SiN (purple line) and the subwavelength NW embedded in a photonic crystal shown in panel c (pink line)

## High yield top-down fabrication of InGaN/GaN NWs

We have demonstrated that selective-area sublimation (carried out in a MBE chamber) together with electron beam lithography or displacement Talbot lithography can be a powerful and versatile method to realize precisely defined GaN-based NW arrays in a top-down approach. We have shown that it not only allows for high yield and homogeneity on a macroscale but also for a fine nanoscale control in terms of position, shape, and dimensions.

Despite this top-down approach, we have been

able to demonstrate the high material and optical quality of these NWs. The existence of intrinsic Fabrv-Pérot resonances in thick NWs (4-7 μm) lead to room-temperature lasing in the near-ultraviolet range. We have shown that subwavelength NWs including precisely posiquantum tioned InGaN disks can be integrated into a hybrid nanophotonic platform.

## **Breakthroughs**

First demonstration of InGaN/GaN NW-induced nanocavities in slotted SiN photonic crystal.

## **Perspectives**

Taking advantage of the ultrahigh vacuum environment in which the sublimation is carried out to realize more complex NW designs, including core-shell and hollow-core structures as well as radial heterostructures.